

Applications of Atomic Layer Deposition in the Modification of Carbon Nanotubes

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Outline

- Motivation
- What is a Thin Film?
- Atomic Layer Deposition (ALD) a primer
- ALD of NiO and ex situ reduction
- Results of Coated CNTs
- ALD deposition of Catalyst Layer for CNT growth
- Stray light suppression results
- Conclusions Q&A



Motivation – Stray Light Control



High contrast scene; Greenland

- Z306 absorbs 96%; our current piBlack nanotube formulation absorb > 99.5% from the visible to FIR
- Improving stray light performance of surface treatments can result in exponential stray light reduction at focal plane
 - Enabling new scientific observations with higher – Signal-Noise Ratio - S/N
 - Potentially doubling observational efficiencies in high contrast scenes such as those common in Earth science
 - Simplifying stray light designs by reducing number of controls required for equivalent performance



Motivation – Stray Light Control

- Electron mobility in plane of carbon hexagonal matrix is high effectively creating electron gas behavior similar to a metal
- Light interacts with the electrons but confinement in lattice plane results in absorption and thermalization of energy
- This high electron mobility and confinement results in high absorption with little specular reflection



Formation of single and multi-walled carbon nanotubes from graphene. The graphene sheet on the left is rolled to form a single walled nanotube (middle) and multi-walled carbon nanotube (right).



Thermal CVD Growth of CNTs





NASA

Stray Light Control – Design Parameters

- Parameters for optimization of light absorption
 - Low density; achieving an effective index of refraction approaching 1 vs graphite (n=4.4) allows reflection at interface to be minimized
 - Minimization of amorphous carbon
 - Length; long enough to absorb light that gets into nanotube layer
 - Orientation; vertically aligned nanotubes are significantly better absorbers than randomly oriented formulations
 - Increasing surface roughness of substrate can improve absorption by decreasing interface reflectance as well
- These parameters can be tuned during the growth process by adjusting:
 - Catalyst thickness, gas flow and composition, substrate preparation



Electron Microscope



Applications and Challenges



Goddard in situ Formaldehyde Laser Induced Fluorescence Experiment (Tom Hanisco-PI)



Challenges:

Coating 3D baffles and the inside of cylindrical tubes with catalyst and controlling gas flow during CVD

The fluorescence detection cell of the Goddard in situ formaldehyde LIF experiment is shown with a cut-away view. The laser excites the sampled air in the center of the cell.



Test 3 meters Mass

Constellation of 3 Sciencecraft with linked Telescopes

Applications and Challenges

Laser Interferometer Space Array (LISA) Gravity Wave Sensor (Telescope PI – Jeffrey Livas)







- LISA Stray Light Challenge
 - Telescope used in duplex
 - Tx beam is 10⁹x intensity of Rx Beam
 - Tx beam reflected/scattered off of center of telescope secondary mirror (SM) must be suppressed by 10⁹



Applications and Challenges



Solar Coronagraph – PI Doug Rabin



Challenge: 3D Catalyst Deposition, CVD flow control Solution: Catalyst sputtering, tapered boat



https://www.nasa.gov/content/goddard/nasa-ultra-black-nano-coating-to-beapplied-to-3-d-new-solar-coronagraph/#.Vj_a0Uar8ZM







Applications and Challenges

Spherical Occulter Coronagraph CubeSat (SpOC Cube) – PI Phil Chamberlin





Three titanium spheres from ½" to 3" in diameter were fabricated to provide pathfinder elements for testing the theory Challenges to fabricating spheres include:

- 1. Uniformly depositing catalyst on a sphere during physical vapor deposition
- 2. Controlling the gas flows during the chemical vapor deposition phase to prevent shadowing and uneven growth

https://gsfctechnology.gsfc.nasa.gov/Coronagraph.html



Challenge



The deposition of the catalyst is in terms of: uniformity, thickness control, material regardless of geometry is paramount. Flat surfaces are easy!



What is a Thin Film?

Thin film: thickness typically <1000nm.

Special properties of thin films: different from bulk materials, it may be –

- Not fully dense
- Under stress
- Different defect structures from bulk
- Quasi two dimensional (very thin films)
- Strongly influenced by surface and interface effects











Common Denominator

•Deposition only occurs on substrates that "see" the target.

- Plasma process can damage the substrate
- Poor thickness control
- Poor Step Control

Metal

(a)

•High Pressure High Temperature Environment

Step Coverage Example

Step coverage of metal over non-planar topography.

(a) Conformal step coverage, with constant thickness on horizontal and vertical surfaces.

(b)

Metal

(b) Poor step coverage, here thinner for vertical surfaces.





Atomic Layer Deposition



Atomic Layer Deposition

A thin film"nanomanufacturing" tool that allows for the conformal coating of materials on a myriad of surfaces with precise atomic thickness control.

Based on:

- Paired gas surface reaction chemistries
- Benign non-destructive temperature and pressure environment
 - Room temperature -> 250 °C (even lower around 45 °C)
 - Vacuum





ALD Analogy (Checkers)



Goddard



ALD Analogy Chemistry





ALD

Precursor A + Precursor B \rightarrow Solid film + Gas by-products Cyclic operation: A \rightarrow purge \rightarrow B \rightarrow purge \rightarrow A \rightarrow purge $\rightarrow \cdots$



Atomic-level thickness control ...



... equivalent to a 60 µm layer over a city-sized wafer



ALD Advantageous Property



Artificial trench filled with an ALD nanolamina



Pi LCoOp Catron (1) LFOM 4-30 TM 4-30 TM 4-30 TM 5-30 Subh zur

Schematic of a 3D battery integrated in a Si- substrate

in the battery stack as well as the candidate materials. Knopps, M.C. M. et al., 205 Tenne, 25 (2009) pp. 233-244

Epitaxial Growth

Multilayer consisting of: Al2O3 - 25 nm TiN - 20 nm Al2O3 - 25 nm



Batch Process





Substrate Independence











ALD Material Systems



• Gordon, Roy (2008). Atomic Layer Deposition (ALD): An Enable for Nanoscience and Nanotechnology.

PowerPoint lecture presented at Harvard University, Cambridge, MA.

• Elam, Jeffrey (2007). ALD Thin Film Materials. Argonne National Laboratory



High Aspect Ratio (Radiator Pigments)









NAS

Results





Uncoated Pigment

Coated Pigment



ISS Opportunity - MISSE-FF



The Materials ISS Experiment Flight Facility (MISSE-FF) with MISSE Sample Carriers (MSCs) in the fully open position exposing samples/experiments to the harsh environment of space in low-Earth Orbit (LEO). Image courtesy of Alpha Space.



An earlier MISSE mission



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Q.

Atra. 8, 2018

Catch the Nov 17 Antares Launch from Wallops

Get up early Nov. 15 to view the Northrop Grumman's Antares rocket isunch from the Mid-Atlantic Regional Spaceport at NASA's Walkips Flight Facility.

The NASA Isotops Flight Facility and Virginia's Mid-Atlantic Regional Spaceport are set to support th launch of the Antales socket, canying the company's Cyginus cargo spacecraft to the International Space Station at All an IESS Nov. 15.

The launch may be visible, weather permitting, to residents throughout the East Coast of the United States.

The NASA Visitor Center at Walkips openal at 1 a.m. on isunch day for public viewing. Additional locations for catching the launch are Robert Need Park on Christohague Island or Beach Road spanning the area between Chricoteague and Assamsup Islands. Assamsup: Island National Seathore/Christohague National Walkie Reituge In Vilgina will not be open for viewing the launch.





The numerical values in each colored cirle indicate the time (in seconds) after littoff. This value can be used to determine when the rocket become visible within the associated colored region. Viewing availability is based on clear weather condition.

1000 A 1000



Potential Applications











Reaction Pathway



- During Growth Process Ni(II) Oxide reduces to Ni
- Ni (II) Oxide is Oxygen rich and reduction results in 40% decrease in thickness
- Resulting in Ni Cluster



Experimental Procedures





Reactor Parameters:

Reactor Temperature: 245 C Ni Precursor Temperature: 90 C Argon Flow Rate: 20 SCCM Ozone Weight Percent: 8% Ozone Flow Rate: 20 SCCM Ni Pulse Time: .6 Sec (2*.3 sec) Ni Residence Time: 15 Sec Ozone Pulse Time: .2 Sec Ozone Residence Time: 15 Sec



Hydrogen Reduction: 5 Hours 450 C 5% Hydrogen in Argon Flow Rate 550 sccm



Results - SEM & EDS of Ni coated buckypaper

Cross-sectional, edge view of the coat paper, 500 cycles of NiO – then reduced; mounted in metallographic epoxy: a crack frequently found in infiltrated region.





Results - 500 cycles NiO-reduced

Closer view of the cracked area in the Buckypaper; Ni appears to be throughout the Buckpaper thickness.





500 cycles NiO-reduced

Closer view of the CNT in cracked area; showing less Ni than we would like, and more O than we would like.



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1000 cycles NiO-reduced



Buckypaper subjected to more deposition cycles showing good Ni penetration into the paper.





Composition line scan across 1000 cycles NiO-reduced





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500 cycles NiO-NOT reduced



Spectrum 5

Unreduced sample has twice the O content in the paper.



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Growth of CNT & ALD



Typical Growth of CNTs



ALD of Catalyst (Ni)

Precursors and Reaction Pathway

Substrate + Catalyst + Gas = CNNT Si,Ti, flat, 3d + Iron,Ni + Ethylene





Initial Results









Acknowledgments







Adomaitis Research Group

